US00D968030S

(12) United States Design Patent
Li

(10) **Patent No.: US D968,030 S**
(45) **Date of Patent: ** Oct. 25, 2022**

(54) **MASK**

(71) Applicant: **Hongliang Li**, Shenzhen (CN)

(72) Inventor: **Hongliang Li**, Shenzhen (CN)

(**) Term: **15 Years**

(21) Appl. No.: **29/802,220**

(22) Filed: **Aug. 4, 2021**

(51) **LOC (13) Cl.** **29-02**

(52) **U.S. Cl.**
USPC **D29/108**; D21/660

(58) **Field of Classification Search**
USPC D29/100, 102, 103, 105, 106, 108, 122; D2/500, 501, 502, 503, 505, 506, 508; D24/110.1, 110.2; D21/660
CPC A42B 5/00; A42B 3/18; A42B 3/20; A42B 1/046; A63B 71/08; A63B 71/10; A63B 71/105; A61F 9/04; A61F 9/06; A61F 9/029; A41D 13/11; A41D 13/1107; A41D 13/1161; A41D 13/1169; A41D 13/1176; A41G 7/00; A41G 7/02
See application file for complete search history.

(56) **References Cited**

U.S. PATENT DOCUMENTS

1,309,783	A	*	7/1919	Slawin	A41D 13/11 2/206
1,810,486	A	*	6/1931	Lancaster	A45D 44/22 2/206
D113,429	S	*	2/1939	Mehl	D29/108
D125,339	S	*	2/1941	Jaslow	D21/659
2,677,133	A	*	5/1954	Hoffman, Jr.	A41G 7/00 D21/660
2,716,981	A	*	9/1955	More	A45D 44/12 604/303
D202,431	S	*	9/1965	Turner	D21/660
D278,259	S	*	4/1985	Koper	D21/660
D278,261	S	*	4/1985	Koper	D21/660
D278,737	S	*	5/1985	Koper	D21/660
D335,937	S	*	5/1993	Owens	D21/660
5,713,077	A	*	2/1998	Humbrecht	A42B 1/0182 2/202
D470,551	S	*	2/2003	Lin	D21/660
D494,644	S	*	8/2004	Quinn	D2/869
D538,862	S		3/2007	Carusone	
D670,038	S		10/2012	Andrews et al.	
D763,515	S	*	8/2016	Chang	D29/108
D770,688	S	*	11/2016	Peluso	D29/108
D832,941	S	*	11/2018	Wu	D21/660
D849,330	S	*	5/2019	Now	D29/108
D864,479	S	*	10/2019	Hasegawa	D28/7
D886,369	S	*	6/2020	Hasegawa	D28/7
D888,344	S	*	6/2020	Zhou	D29/108
D891,629	S	*	7/2020	Vetu	D24/209

(Continued)

OTHER PUBLICATIONS

USA In Stock Fast Delivery 】 Cotton Halloween Face Masks For Adults Womens Fashion Washable Breathable Face Mask Reusable Dust Facemasks For Women,https://www.amazon.com/Delivery-Halloween-Washable-Breathable-Facemasks/dp/B08JCKQW4M, brand:Onhuon, Sep. 17, 2020. (Year: 2020).*

Primary Examiner — Elizabeth J Oswecki
(74) *Attorney, Agent, or Firm* — Jeenam Park

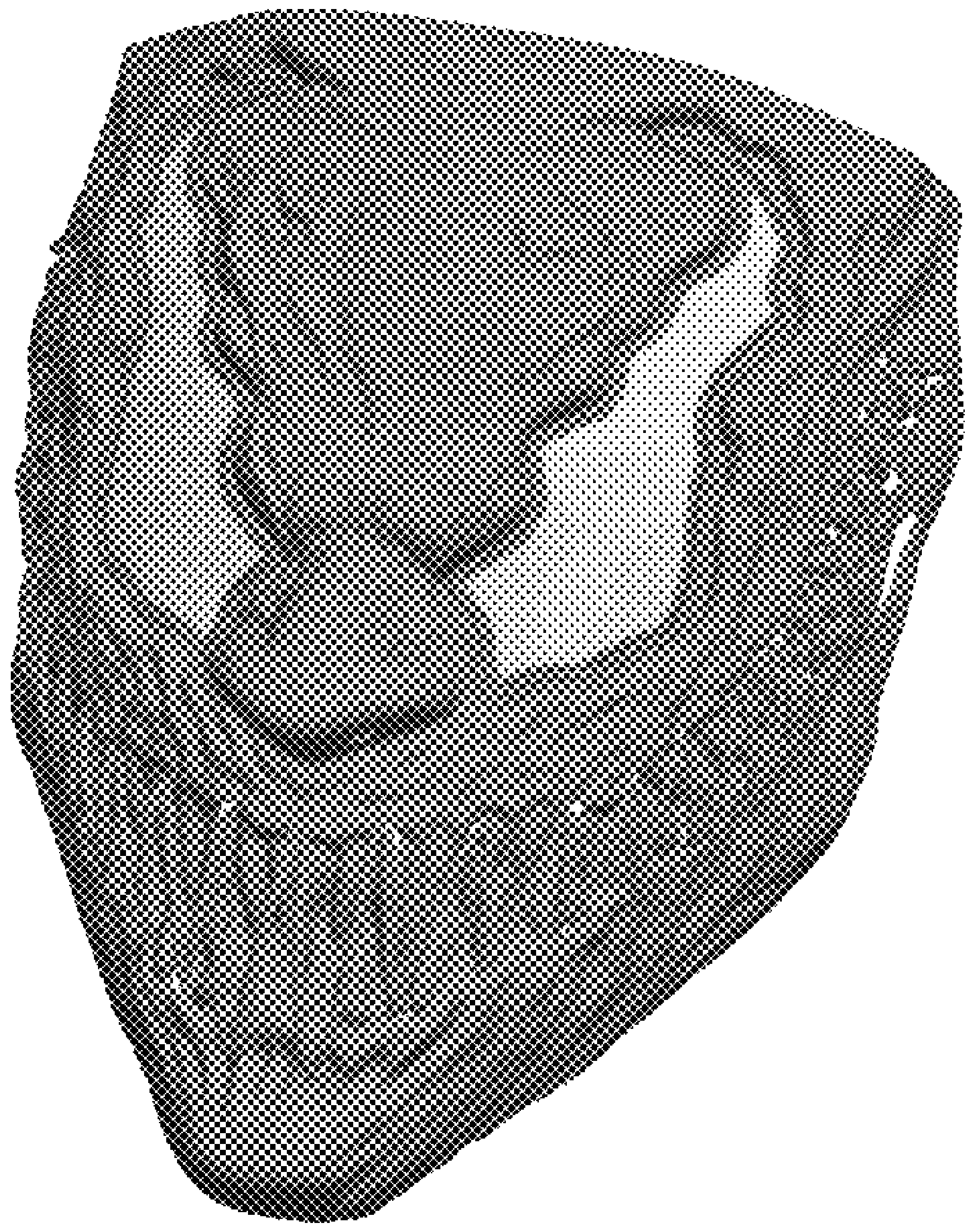
(57) CLAIM

The ornamental design for a mask, as shown and described.

DESCRIPTION

FIG. **1** is a perspective view of a mask, showing my new design;
FIG. **2** is a front view thereof;
FIG. **3** is a rear view thereof;
FIG. **4** is a left side view thereof;
FIG. **5** is a right side view thereof;
FIG. **6** is a top plan view thereof; and,
FIG. **7** is a bottom plan view thereof.

1 Claim, 7 Drawing Sheets



(56) References Cited

U.S. PATENT DOCUMENTS

D894,495	S	*	8/2020	Xie	D29/108
D901,029	S	*	11/2020	Song	D24/209
D914,811	S	*	3/2021	Xu	D21/660
D946,207	S	*	3/2022	Nakamura	D28/7
D946,208	S	*	3/2022	Nakamura	D28/7
D953,698	S	*	6/2022	Zhou	D21/660

* cited by examiner

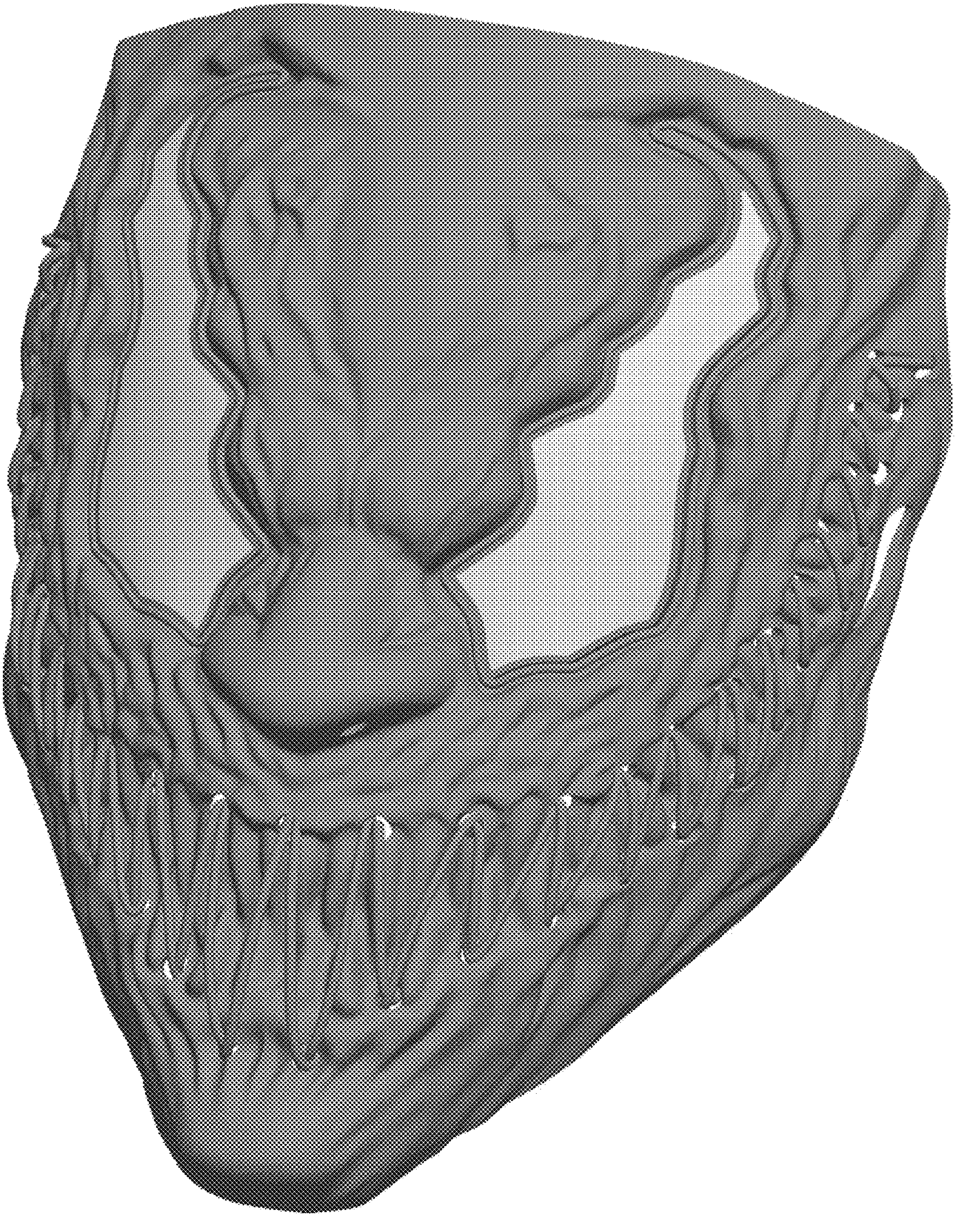


FIG. 1

FIG. 2

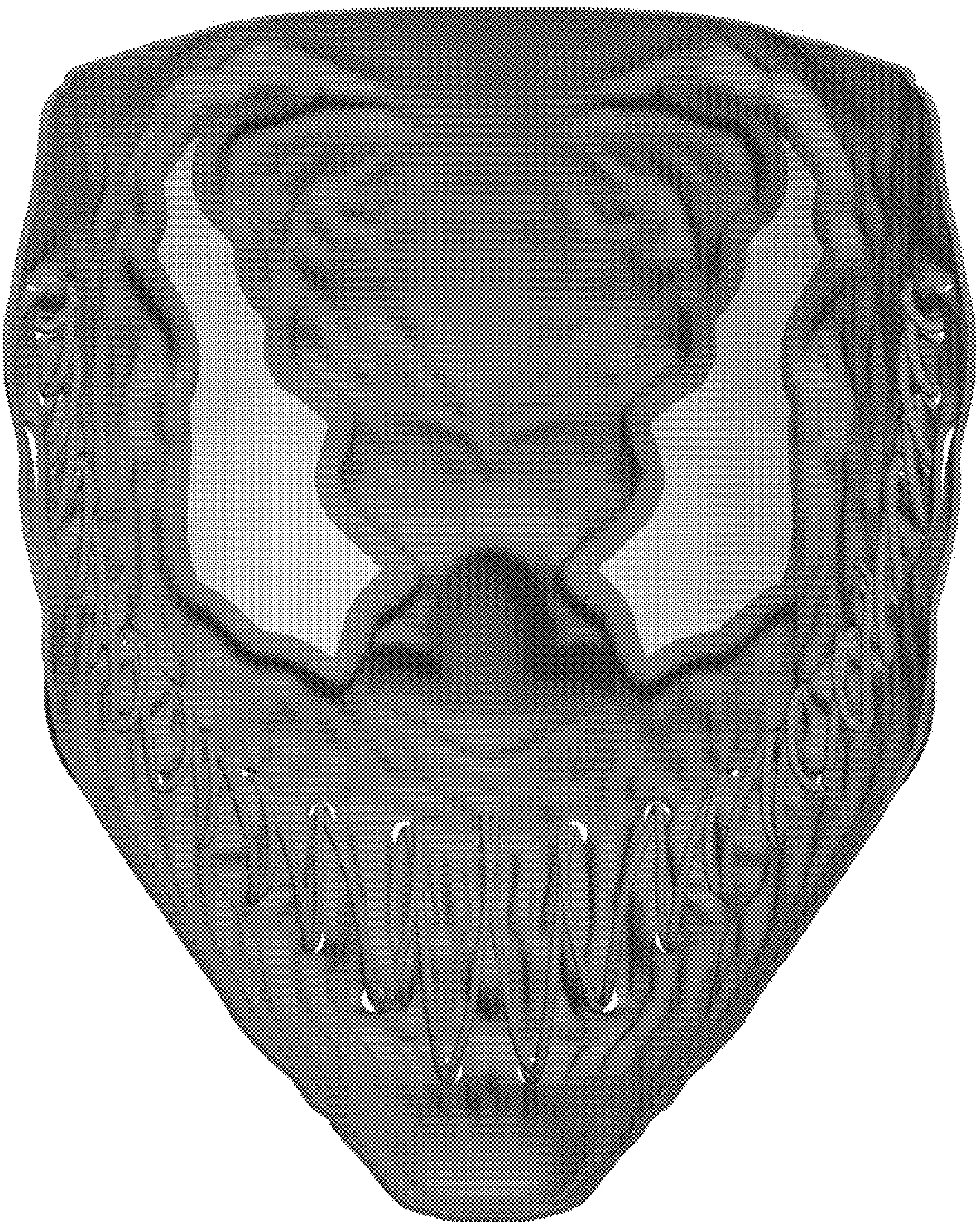


FIG. 3

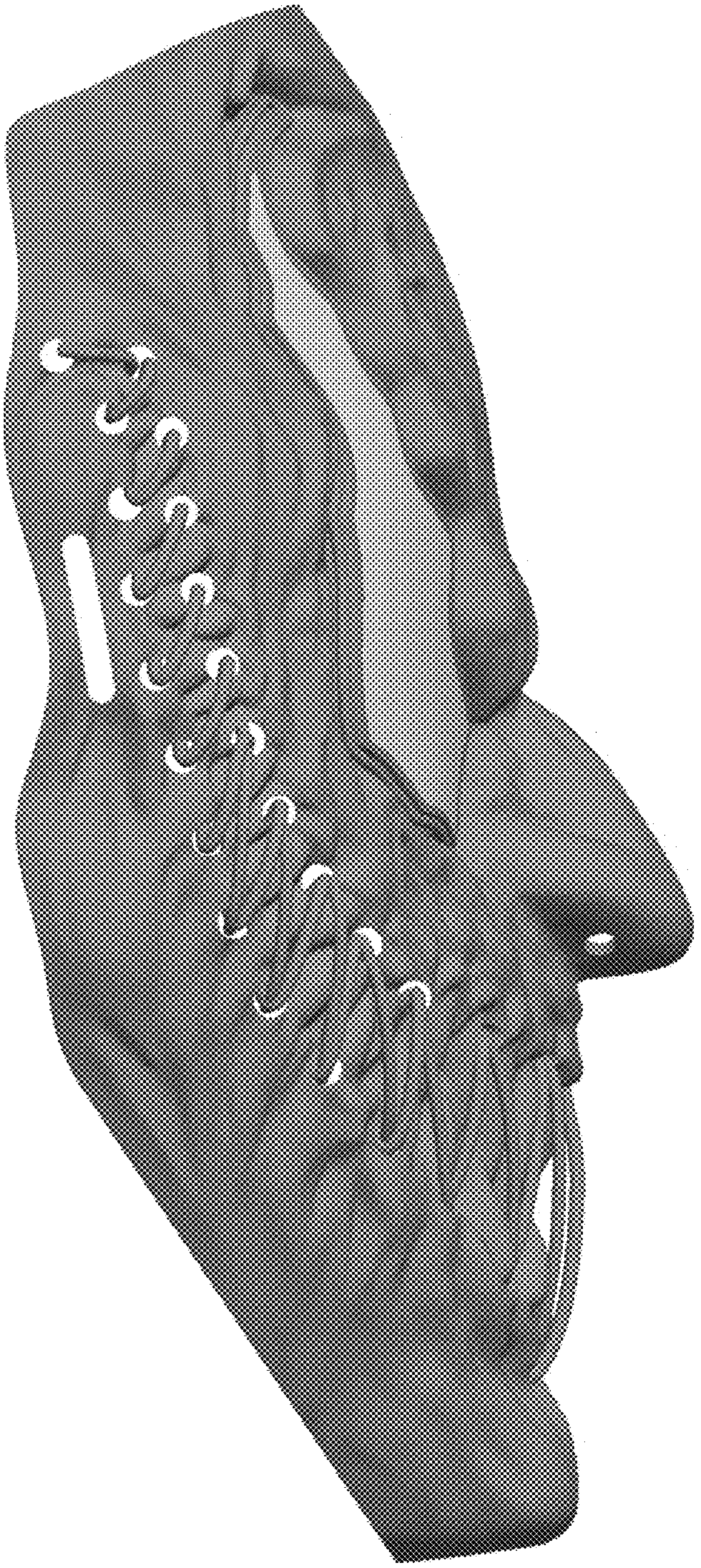


FIG. 4

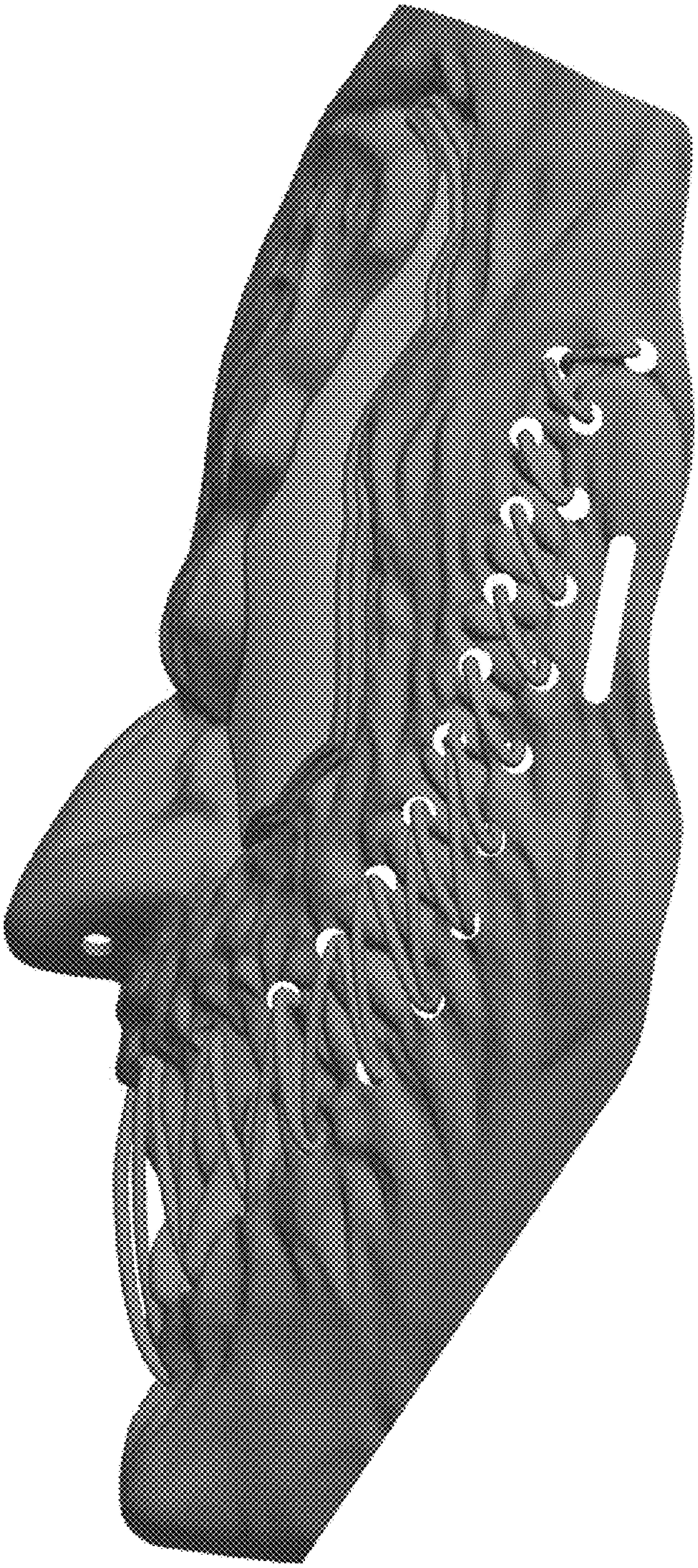


FIG. 5

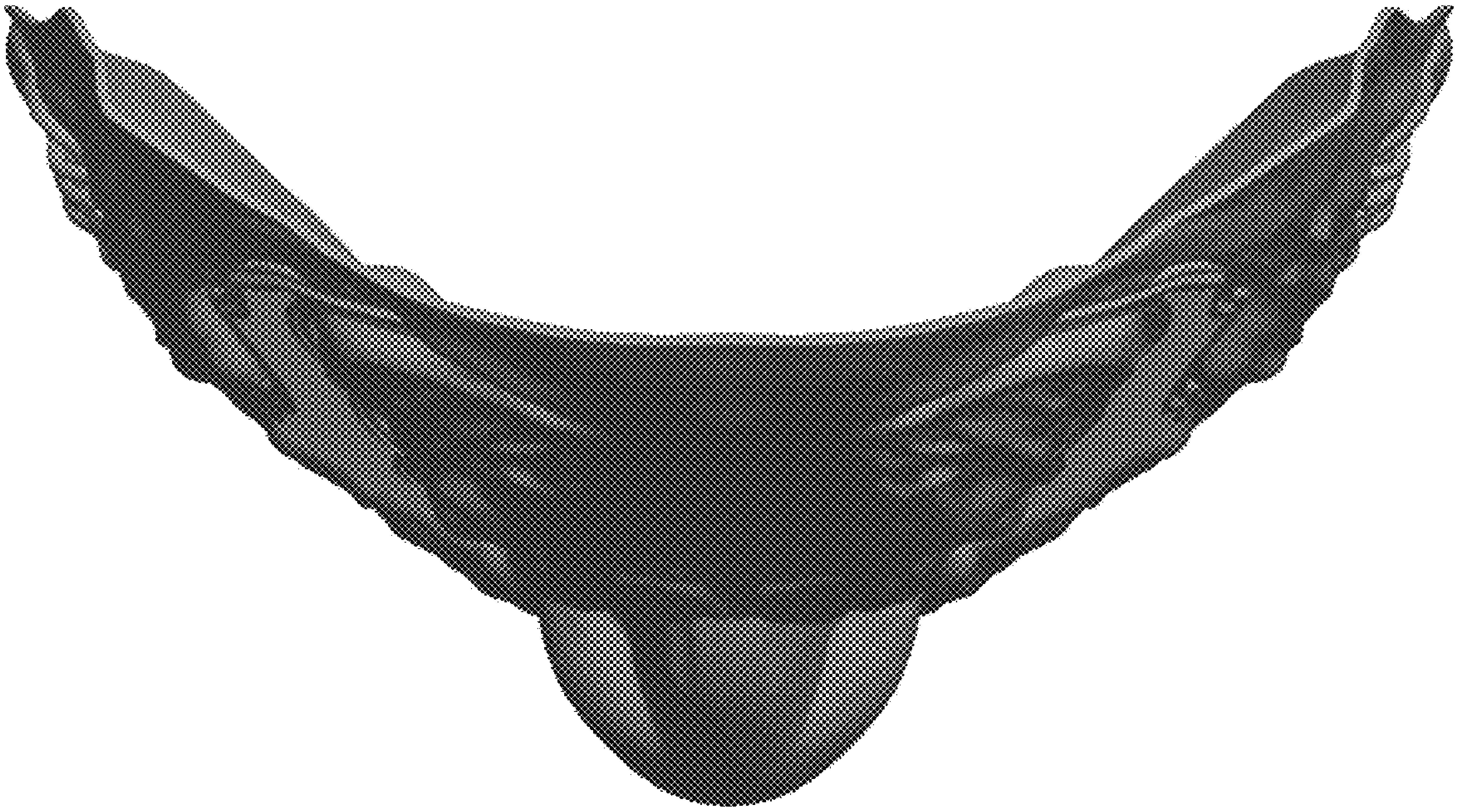


FIG. 6

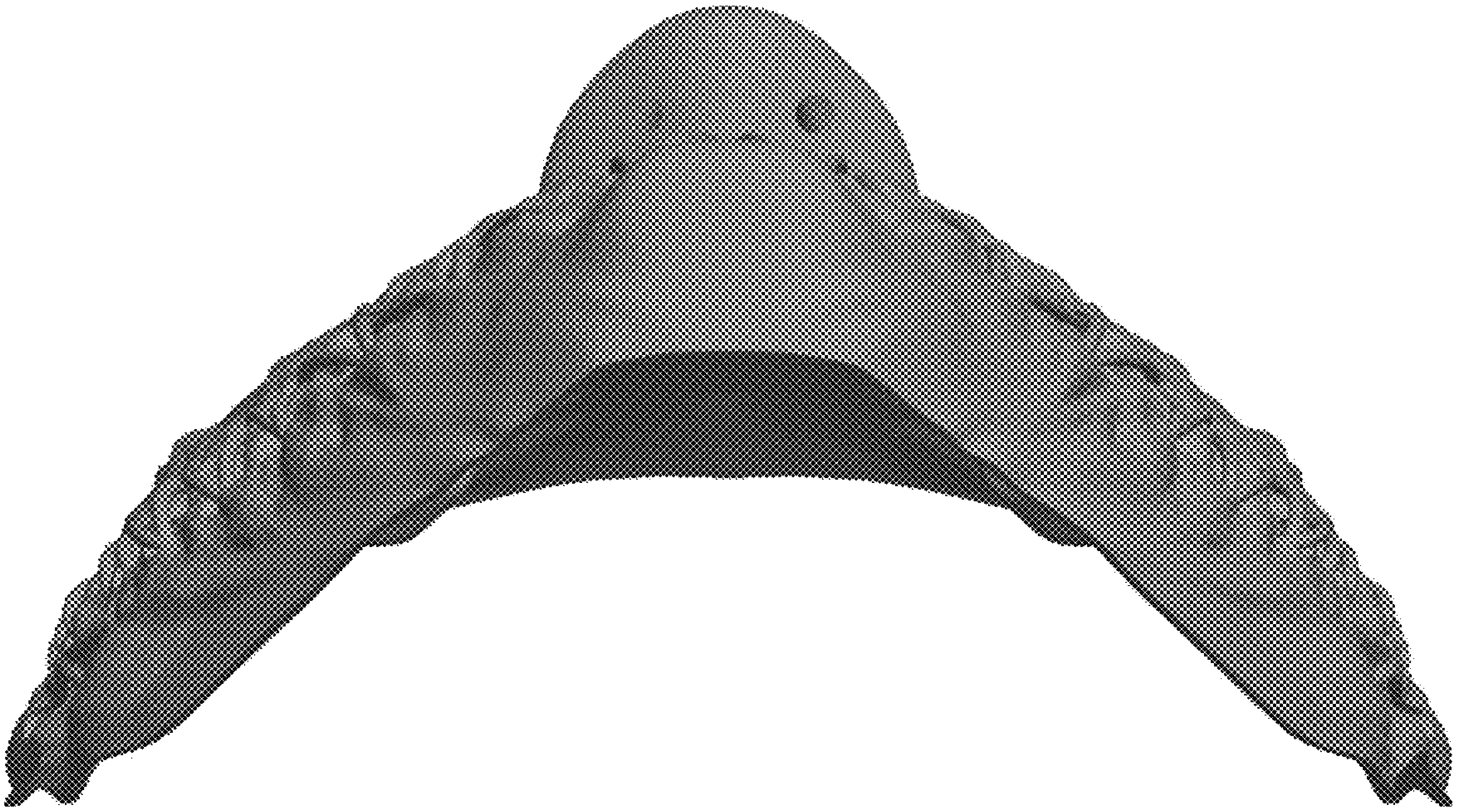


FIG. 7